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TI Method for preparation of high-purity pyrrolidone compounds

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SO Jpn. Kokai Tokkyo Koho, 6 pp.

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AB The compds., e.g., N-methyl-2-pyrrolidone, useful as solvents and for industrial degreasing, defluxing application, etc., are manufd. by heating .gamma.-butyrolactone with NH<sub>3</sub> or an amine compd. in the presence of water as usual, then feeding the mixt. (M) to a distn. tower, distg. in such a way that the residence time of the M at tower bottom maintained at 90-200.degree. is .apprx.10 min to 2 h while removing from the tower head a low-melting fraction contg. water and unreacted amine, from the towel bottom pyrrolidone compd. at 2-15% of introduced materials and from a side line the remaining pyrrolidone compd. The control of towel bottom temp. and residence time is essential for the improvement of product purity.

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ICS B01D003-00; C07D207-267

DT Patent

LA Japanese